Quantifying lateral interactions in gold self-assembled monolayers: The effect of topography and surface concentration

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Background

NORTH

LVX

HAPEL



samples and all steps involving these chemicals were carried out by T. Teitsworth (a

postdoctoral researcher) who wore an apron, face-shield, and gloves.

Surface Concentration $\int \frac{1}{\sqrt{2}} \int \frac{1$

Concentration of ferrocene can be calculated by integrating the area underneath the anodic/cathodic curve

Roughness



- Usage of Laviron's equation to calculate $G\theta$ or lateral interactions
- More negative G θ values indicate repulsive forces between ferrocene molecules
- With increased roughness and surface loading, there are more negative G0 values, which indicate repulsive forces between ferrocene molecules
- Positive G0 values are present at high roughness because of low surface coverage on the electrode

Conclusions

Future Directions

- Modify roughness parameters to have more consistent, equally sized and spaced pits on the surface
- Experiment with lower concentrations of ferrocene and lower roughness values than flat samples to gain broad ranges and extreme values

Beyond the Scope

- Study on a different substrate; quantifying lateral interactions in selfassembled monolayers on silicon with varying topography and surface concentration
- Incorporate carbon dioxide reduction catalysts as a monolayer to understand how lateral interactions affect catalysis

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Method A: 20 nr









 RMS: 2.098 ± 1.50 nm
CV plot shows broadening peaks and indicates roughness on the surface; presence of a double peak suggests different redox environments on the surface

> RMS: 3.112 ± 2.98 nm
> SEM imaging and AFM height analysis shows that roughness values are high because of the formation of silicon nanowires

RMS: 5.195 ± 2.5 nm

SEM imaging of 20 nm

nanoparticles showed

wormhole-like etching,

more variations could

contribute to higher

roughness values